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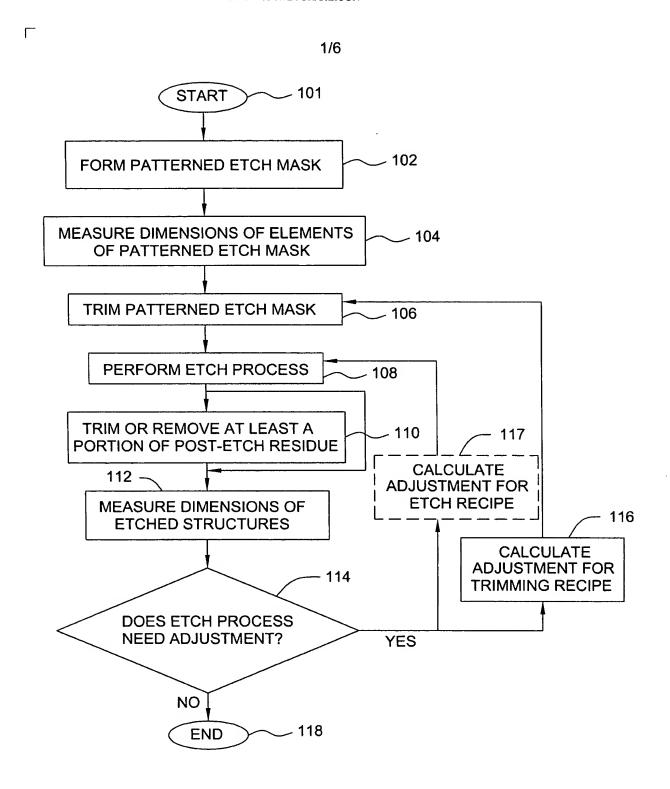


FIG. 1

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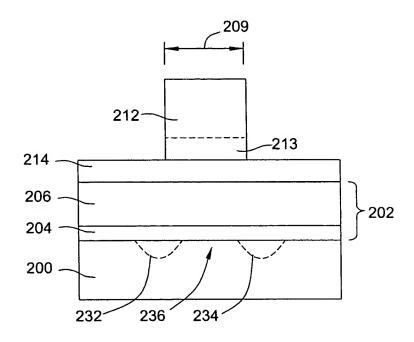


FIG. 2A

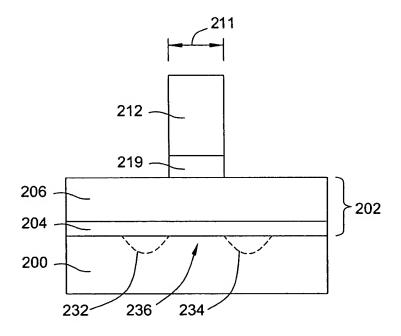


FIG. 2B

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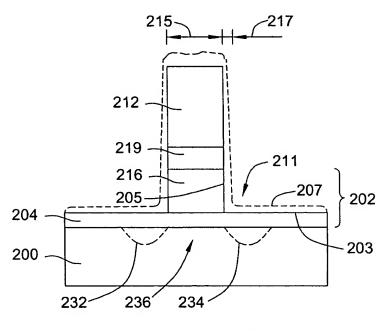


FIG. 2C

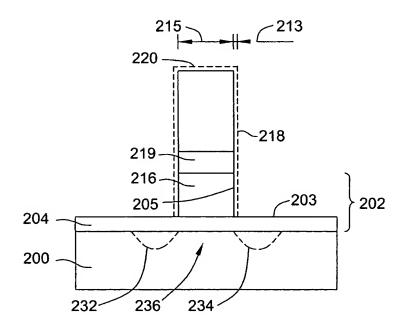
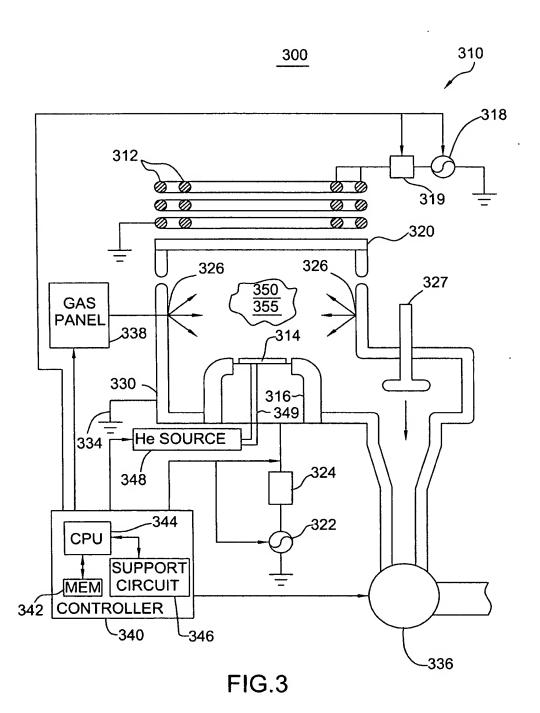


FIG. 2D

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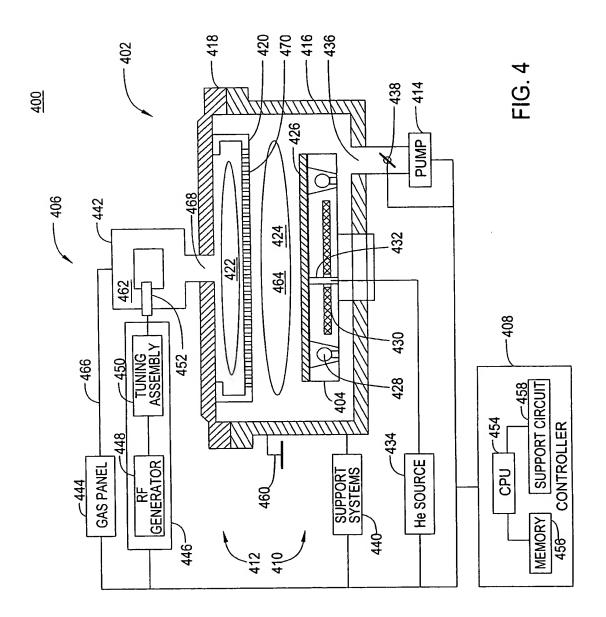
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